



EP-12

Ellipsometric Porosimeter



EP-12 System

This configuration of Ellipsometric Porosimeter has the capability of measuring 200 and 300 mm wafers. Compact in size, and the very user friendly operation, make this a perfect tool for Research and Development on porous Low-K ILD materials.

Superior Performance

The Ellipsometric Porosimetry method is more simple and more fast than PALS, SANS/SXR, or other techniques used in determining Full Porosity, Pore Size Distribution, Pore Interconnectivity and Barrier performance.

On top of this, Young Modulus of inorganic ultra low-K dielectrics can also be determined. The accuracy of pore size determination is better than 0.2 nm.

The Perfect Technology

All measurements can be carried out in a film deposited on top of a silicon wafer or any smooth solid substrate. Because a laser probe is used, small surface areas can be analyzed. Therefore EP can be used on patterned wafers as it is a non-destructive technique.

Metrology Options

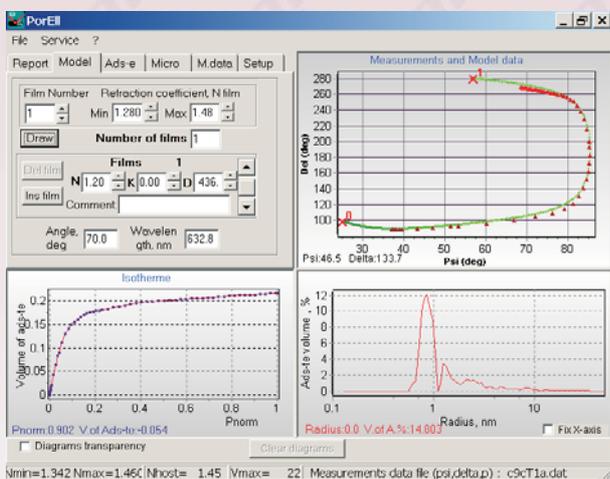
The EP-12 can be configured to utilize a single wave length laser source for small surface areas, faster operation and porosity mapping, or a multi wave length source to give more information on extra characteristics like film swelling.

EP-12 Specifications

PorEl Software

The software was developed to, if preferred, run on a remote computer if the EP-12 is hooked up to a network. It calculates open porosity, skeleton refractive index (necessary for calculation of full porosity), pore size and pore size distribution in approximately 3-5 seconds after receiving the data file from the system and loading the fitting parameters.

On top of this, it calculates multi-layer systems and therefore gives information on Barrier Layer performance and the so-called Pore Killers.



Facilities and Engineering Specifications

Wafer size:	200 and 300 mm wafers and samples
Range of the film thickness:	> 50 nm
Pore size:	0.2 - 50 nm
Ellipsometer:	$\lambda = 6328 \text{ \AA}$ $\lambda = 3500 - 8500 \text{ \AA}$
Base vacuum:	10^{-6} mBar
Measurement temperature:	20°C
Organic adsorptives:	toluene, heptane, isopropyl alcohol
Nitrogen:	1m ³ /h, 1-2 Bar
CD Air:	2m ³ /h, 6-7 Bar
Exhaust	5m ³ /h Min
Electrical:	110/220VAC, 32A, 50/60Hz, Single Phase
Dimensions:	System: 1600 x 1388 x 1630 mm Rack: 600 x 600 x 1000 mm
Net Weight:	System: 320 kg Rack: 90 kg



XPEQT, AG

Chemin de Buchaux 38, 2022 Bevaix, Switzerland
phone: +41 32 835 55 69
fax: +41 32 835 55 74

e-mail address: info@xpeqt.com

Web: <http://www.xpeqt.com>